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Atty Docket No. KLA1P117X1A/P1151/2 Application No.: 10/785,396

Information Disclosure Statement By Applicant Applicant: Mieher, et al.

(Use Several Sheets if Necessary)

Filing Date February 23, 2004 Group 2877

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GS	A	6,350,548 B1		Ausschnitt, et al.	356	401	11/20/95
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GS	C	4,757,207	07/12/88		382	145	02/13/03
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GS	F	6,486,954	11/26/02	Mieher et al.	356	401	09/01/00
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	A9	6,023,338	02/08/00	Bar	eket	356	401	07/12/96			
	A10	4,820,055	04/11/89	Mu	ller	356	401	08/25/86			
	A11	6,013,355	01/11/00	Che	en et al.	428	209	12/30/96			
	A12	5,343,292	08/30/94	Bru	eck et al.	356	363	10/19/90			
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	A14	6,323,560	11/27/01	Naı	rimatsu et al.	257	798	01/27/00			
	A15	4,631,416	12/23/86	Tru	tna, Jr.	250	548	12/19/83			
	A16	4,828,392	05/09/89	No	mura et al.	356	401	03/10/86			
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	A18	4,848,911	07/18/89	Ucl	nida et al.	356	356	06/11/87			
	A19	6,197,679	03/06/01	Hat	tori	438	636	03/23/99			
	A20	5,172,190	12/15/92	Kai	ser	356	401	01/11/91			
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	A23	6,420,791	07/16/02	Hu	ang et al.	257	797	11/23/99			
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	B4	5,883,710	07/10/95	Nik	coonahad et al.	356	237.2	06/10/95			
	B5	6,081,325	06/27/00	Les	lie et al.	356	237.2	06/03/97			
	B6	4,818,110	04/04/89	Dav	vidson	356	358	05/06/86			
	В7	5,112,129	05/12/92	Dav	vidson et al.	356	359	03/02/90			
	В8	5,889,593	02/30/99	Bar	eket	356	445	02/26/97			
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	B10	6,633,831	10/14/03	Nik	coonahad et al.	702	155	09/20/01			
	B11	6,420,971	07/16/02	Lec	k et al.	340	542	06/22/00			
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	B15	6,013,355	01/11/00	Che	en et al.	428	209	12/30/96			
	B16	4,703,434	10/27/87	Bru	inner .	364	488	04/24/84			
	B17	5,783,342	07/21/98	Yaı	mashita et al.	430	30	12/27/95			
	B18	5,801,390	09/01/98	Shi	raishi	250	559.3	02/07/97			
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	B20	5,182,455	01/26/93	Mu	raki	250	548	05/11/92			
	B21	6,476,920	11/05/02	Sch	einer et al.	356	630	06/26/00			
	B22	5,189,494	02/23/93	Mu	raki	356	401	01/08/92			
	B23	5,316,984	05/31/94	Lec	ourx	437	250	03/25/93			
	B24	5,327,221	07/05/94	Sai	toh et al.	356	355	07/29/92			
V	B25	5,666,196	09/09/97	Ish	ii et al.	356	356	11/17/95			
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	C7	5,340,992	08/23/94	Ma	tsugu et al.	250	548	11/18/92
	C8	6,077,756	06/20/00	Lin	et al.	438	401	04/24/98
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	C13	4,332,473	06/01/82	One	0	356	356	11/22/80
	C14	4,750,836	06/14/88	Ste	in	356	399	09/18/86
	C15	5,596,413	01/21/97	Sta	nton et al.	356	401	08/17/95
	C16	4,929,083	05/29/90	Bru	inner	356	400	03/20/89
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	C18	2002/0149782	10/17/02	Ray	mond	356	616	02/28/02
	C19	2002/0072001	06/13/02	Bro	own et al.	430	30	05/04/01
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	D3	JP 60-126881	86.07.06	JAPAN	H01S	3/18		X
	D4	JP 63-248804	10.17.88	JAPAN	C08F	10/00		X
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	D6	WO/95/02200	19.01.95	WIPO	G02B	5/18	X	
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	D8	WO/03054475	03.07.03	WIPO	G01B	11/06	X	
	D9	WO/0218871	07.03.02	WIPO	G01B	11/27	X	
	D10	WO 02/065545	22.08.02	WIPO	H01L	21/66	X	
	D11	WO/0215238	21.02.02	WIPO	H01L	21/00	X	
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	D13	WO 02/35300	02.05.02	WIPO	G05B	19/00	X	
	D14	WO 02/25723	28.03.02	WIPO	H01L	21/66	X	
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